

Amendment
U.S. Patent Application No. 09/900,533

IN THE CLAIMS:

1. (Currently amended) An aqueous-based composition comprising from about 40% to about 95% by weight cesium formate and at least one chelating agent, wherein said aqueous-based composition has a pH of from about 9 to about 14.
2. (Original) The composition of claim 1, wherein the cesium formate is present in an amount of from about 3 M to about 12 M and said at least one chelating agent is present in an amount of from about 0.2 M to about 1.0 M.
3. (Original) The composition of claim 1, wherein said chelating agent is at least partially ionic.
4. (Original) The composition of claim 1, wherein said chelating agent is cationic.
5. (Original) The composition of claim 1, wherein said chelating agent is anionic.
6. (Original) The composition of claim 1, further comprising potassium formate.
7. (Original) The composition of claim 1, wherein said pH of said composition is from about 11 9 to about 13 14.
8. (Original) The composition of claim 1, wherein said chelating agent is diethylenetriamine pentaacetic acid optionally having carboxylate anions.
9. (Currently amended) The composition of claim 1, wherein said composition has a specific gravity density of from about 1.2 g/cm³ to about 2.4 g/cm³.
10. (Original) The composition of claim 1, wherein said aqueous-based composition is less than fully saturated with said cesium formate.

11-24. (Withdrawn)

Amendment

U.S. Patent Application No. 09/900,533

25. (Currently amended) A completion fluid comprising at least one alkali metal formate, and at least one acid, ~~or chelating agent or both and optionally containing~~ at least one surfactant, ~~or mutual solvent, or both and optionally at least one chelating agent, wherein said at least one alkali metal formate is present in an amount of from about 40% to about 95% by weight.~~

26. (Original) The completion fluid of claim 25, wherein said alkali metal formate comprises cesium formate.

27. (Original) The completion fluid of claim 25, wherein said alkali metal formate comprises cesium formate and potassium formate.

28. (Original) The completion fluid of claim 25, wherein said alkali metal formate comprises potassium formate.

29. (Original) The completion fluid of claim 25, wherein said acid is formic acid or an acid derivative thereof.

30. (Original) The completion fluid of claim 25, wherein said surfactant or mutual solvent or both are present.

31. (Original) The completion fluid of claim 30, wherein said surfactant or mutual solvent comprises a mixture of an ethylene oxide/propylene oxide adduct of an acrylate copolymer, polymeric hydroxyethylethylene urea, monobutyl ethylene glycol, ethoxylated long chain alcohols, sulfated long chain alcohols, or combinations thereof.

32. (Currently amended) The completion fluid of claim 25, wherein said completion fluid has a specific gravity density of from about 1.2 g/cm³ to about 2.4 g/cm³.

33. (Original) The completion fluid of claim 25, wherein the alkali metal formate is present in an amount of from about 3 M to about 12 M and said at least one acid is present in an

Amendment

U.S. Patent Application No. 09/900,533

amount of from about 0.2 M to about 12 M.

34. (Currently amended) A spent completion fluid comprising at least one alkali metal formate, at least one acid, at least one surfactant, or chelating agent or both and a dissolved or solubilized filter cake, and optionally, at least one surfactant or mutual solvent, or both chelating agent, wherein said at least one alkali metal formate is present in an amount of from about 40% to about 95% by weight.

35. (Original) The spent completion fluid of claim 34, wherein said filter cake comprises a fluid loss agent.

36. (Original) The spent completion fluid of claim 34, wherein said filter cake comprises calcium carbonate or at least one alkaline earth metal sulfate or both and optionally at least one fluid loss agent.

37. (Original) The spent completion fluid of claim 34, wherein said filter cake further comprises drilling fines.

38. (Original) The spent completion fluid of claim 34, wherein said alkali metal formate comprises cesium formate.

39. (Original) The spent completion fluid of claim 34, wherein said alkali metal formate comprises cesium formate and potassium formate.

40. (Original) The spent completion fluid of claim 34, wherein said alkali metal formate comprises potassium formate.

41. (Original) The spent completion fluid of claim 34, wherein said alkali metal formate is present in an amount of from about 3 M to about 12 M and said at least one acid is present in an amount of from about 0.2 M to about 12 M.

Amendment

U.S. Patent Application No. 09/900,533

42. (Original) The spent completion fluid of claim 34, wherein said acid comprises formic acid or an acid derivative thereof.

43. (Original) The spent completion fluid of claim 34, wherein said surfactant or mutual solvent comprises a mixture of a ethylene oxide/propylene oxide adduct of an acrylate copolymer and polymeric hydroxyethylethylene urea.

44-52. (Withdrawn)

53. (Original) The completion fluid of claim 25, wherein the alkali metal formate is present in an amount of from about 3 M to about 12 M and said at least one chelating agent is present in an amount of from about 0.2 M to about 1.0 M.

54. (Original) The completion fluid of claim 25, wherein said chelating agent is at least partially ionic.

55. (Original) The completion fluid of claim 25, wherein said pH of said completion fluid is from about 9 to about 14.

56. (Original) The completion fluid of claim 25, wherein said chelating agent is diethylenetriamine pentaacetic acid optionally having carboxylate anions.

57. (Original) The spent completion fluid of claim 34, wherein the alkali metal formate is present in an amount of from about 3 M to about 12 M and said at least one chelating agent is present in an amount of from about 0.2 M to about 1.0 M.

58. (Withdrawn)

59. (Original) The completion fluid of claim 25, wherein said surfactant or mutual solvent comprises at least one sodium or ammonium salt of acrylic acid copolymer, optionally containing one or more alkylene oxide adducts.

Amendment

U.S. Patent Application No. 09/900,533

a2

60. (New-Re-presented-formerly dependent claim #4) An aqueous-based composition comprising cesium formate and at least one chelating agent, wherein said chelating agent is cationic.